aplanoXX

High NA objectives compensating spherical aberration induced when focusing in media, with protective window

Applications:

- **Microprocessing sapphire, fused silica, glass, Si, SiC**
- **3D micro- and nanofabrication**
- **Nanostructuring in optical data storage and recording polarization converters**
- **Selective Laser Etching**
- **Waveguide recording**
- **Dicing**
- **Microscopy**

Specifications

		aplanoXX_NA0.8_D20	aplanoXX_NA0.5_D9
Description		Objectives of aplanatic design with - function of compensation of spherical aberration that occurs when focusing in transparent media - protective window	
Numerical aperture (NA)		0.8	0.5
Clear Aperture, mm		20	9
Focal length, mm		12.5	8.5
Protective Window		D12, replaceable, in holder	
Working Distance, mm	- with window	1.6	4.4
	- without window	2.5	5.5
Range of focusing depth in fused silica*, µm		0 ... 4000	0 ... 1000
Spectral band, nm		_1030: 1020 – 1100 _800: 770 - 900 _515: 510 – 545 _800 / 1030: 770 – 900 / 1020 – 1100 other wavelengths available on request	
Angular field of view *		± 0.3°	± 1°
Recommended maximum pulse energy		100 mJ at 5 ns 300 µJ at 1 ps	25 mJ at 5 ns 100 µJ at 1 ps
Mounting		C-Mount (1”-32 UN 2A), external other threads available on request	
Diameter, mm		44	32
Length with window holder, mm		54	36 (42 with adapter)

* - by diffraction limited focusing.

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